

*Calc*  
perfluoroalkylamine oxide, perfluoroalkylethylene oxide adduct, and fluorine-containing organosiloxane compounds.

*Ar  
cont*  
10. A resist material according to claim 1 wherein said one or more surfactants having a fluorine substituent is present in an amount ranging from 10 to 2,000 ppm.

11. A resist material according to claim 1 wherein the weight ratio of the non-ionic surfactant having neither a fluorine substituent nor a silicon containing substituent to the surfactant containing a fluorine substituent is 0.1 or greater.

12. A resist material according to claim 11 wherein the weight ratio of the non-ionic surfactant having neither a fluorine substituent nor a silicon containing substituent to the surfactant containing a fluorine substituent ranges from 0.1 to 100.

*Sub  
Bz*  
13. A method for forming a pattern on a substrate comprising:  
coating a resist material on a substrate, the resist material comprising one or more surfactants having a fluorine substituent and one or more non-ionic surfactants having neither a fluorine substituent nor a silicon-containing substituent;

subjecting the substrate to heat to treat the substrate;

exposing the substrate through a photomask to radiation selected from the group consisting of high energy radiation having a wavelength of 500 nm or less, X-ray radiation, and electron beam radiation;

optionally heat treating the substrate; and

developing the substrate in a developing solution.

14. A method according to claim 13 wherein said non-ionic surfactant is one or more compounds selected from the group consisting of polyoxyalkylene alkyl ether esters, polyoxyalkylene alkyl ether, polyoxyalkylene dialkyl ether, polyoxyalkylene aralkyl alkyl ether, polyoxyalkylene aralkyl ether, polyoxyalkylene diaralkyl ether, and polyoxyalkylene laurylates.

15. A method according to claim 13 wherein the resist material is a chemically amplified resist material.

16. A method according to Claim 14 wherein the resist material is a chemically amplified resist material.

#### Remarks

Claims 1-4 and 9-16 are presented for examination in the above-referenced application. Claims 5-8 are canceled for rewriting purposes and are re-drafted as Claims 13-16. Applicants respectfully request substantive examination on the merits.

Respectfully submitted,



Robert J. Smith

Registration No. 40,820

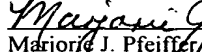
Correspondence Address:  
USPTO Customer No.: **20792**  
Myers Bigel Sibley & Sajovec  
Post Office Box 37428  
Raleigh, NC 27627  
Telephone (919) 854-1400  
Facsimile (919) 854-1401

#### **CERTIFICATE OF EXPRESS MAILING**

Express Mail Label No. EL733093962US

Date of Deposit: May 8, 2001

I hereby certify that this correspondence is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 CFR 1.10 on the date indicated above and is addressed to Box Patent Application, Commissioner For Patents, Washington, DC 20231.



Marjorie J. Pfeiffer

Date of Signature: May 8, 2001